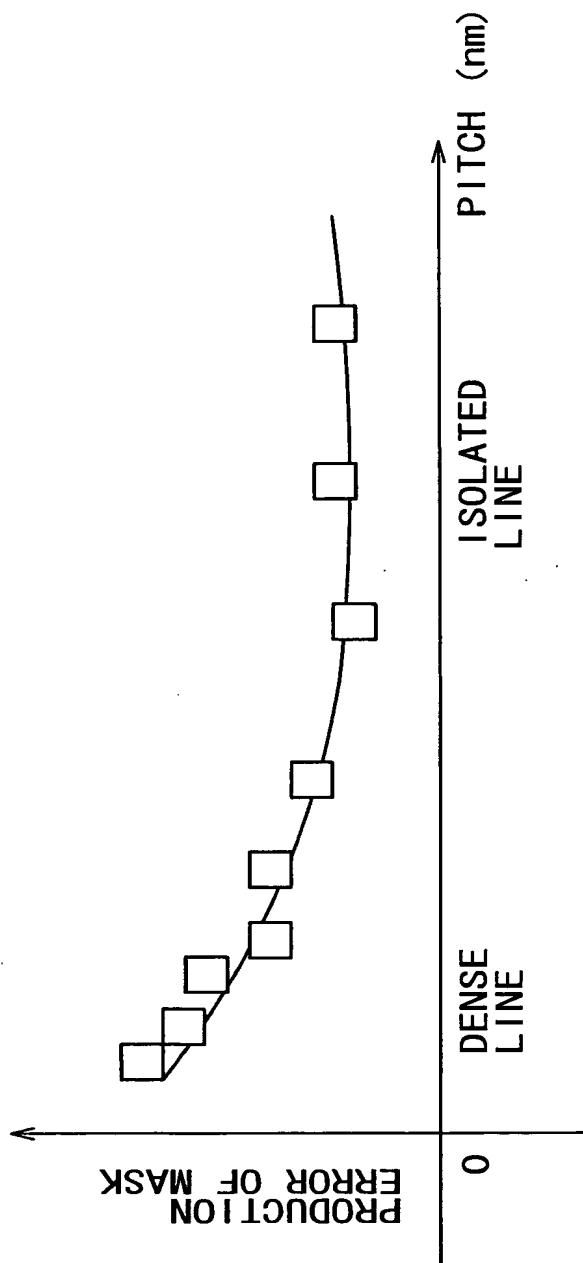


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METHOD FOR CORRECTING MASK
Inventor: Ken Ozawa
Attorney Docket No.: 075834.00464
Robert J. Depke, Holland & Knight LLC - (312) 263-3600

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FIG. 1

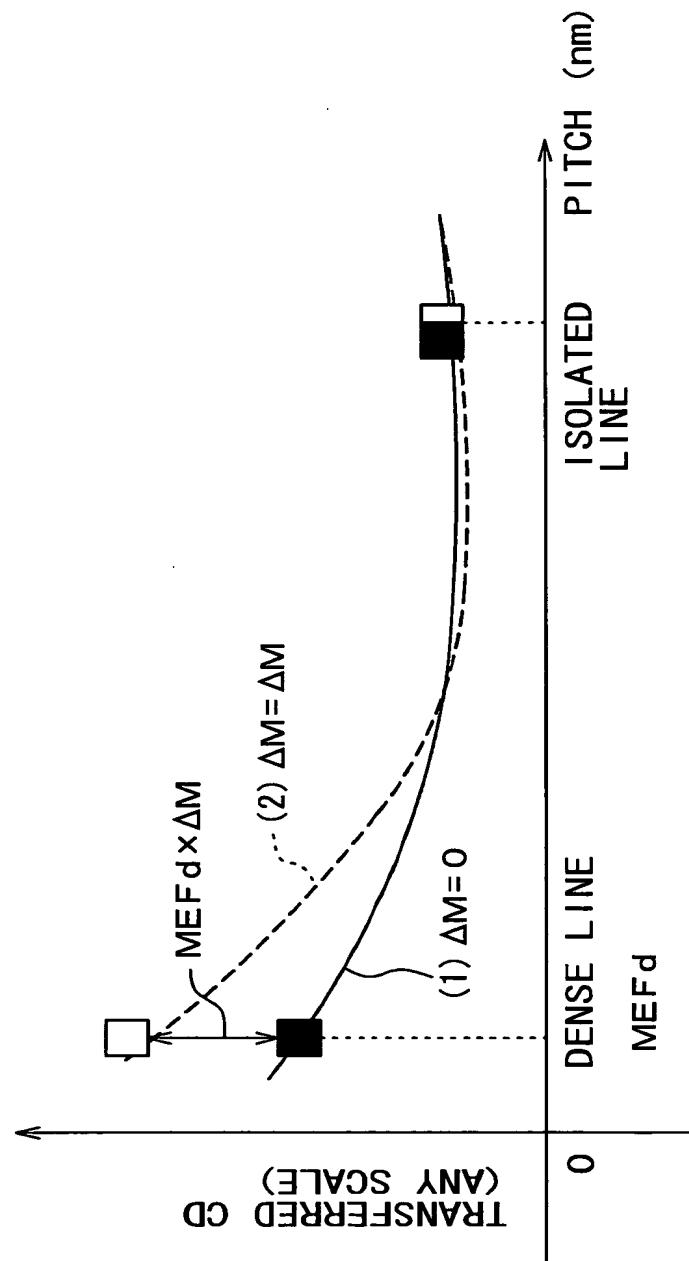


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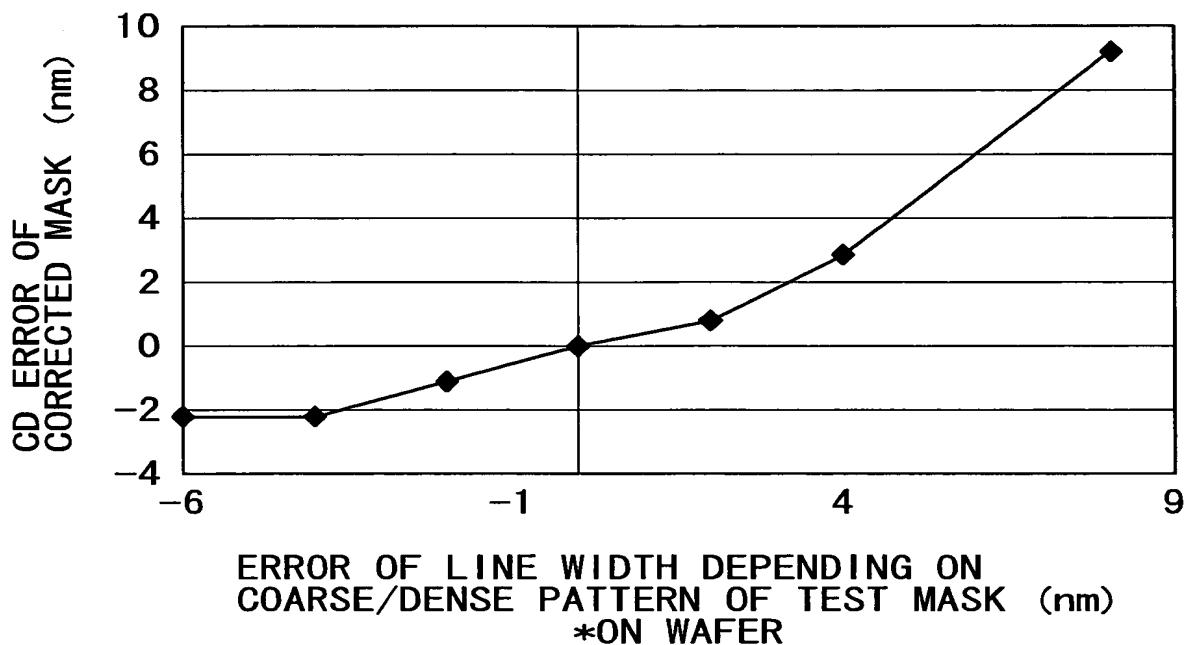
F I G. 2



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F I G. 3



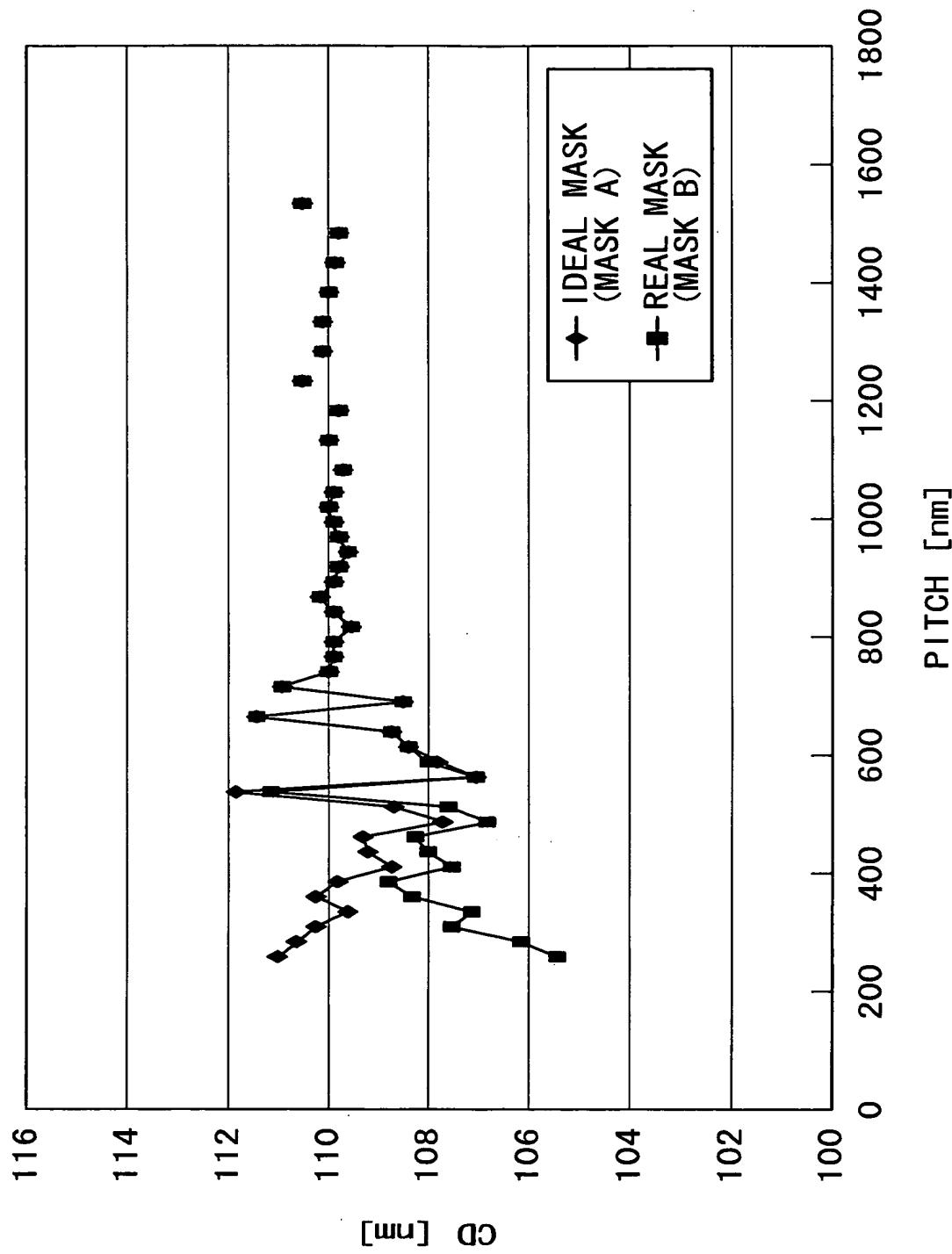
F I G. 4

DIMENSIONAL ERROR OF COARSE/DENSE MASK (ON W)	CALCULATED CORRECTED VALUE OF MASK	DIMENSIONS OF CORRECTED MASK (WHEN ERROR DEPENDING ON COARSE/DENSE IS REPRODUCED)	CD ERROR OF WAFER CD WHEN CORRECTED MASK IS TRANSFERRED
-6	132	126	-2.2
-4	130	126	-2.2
-2	128.5	126.5	-1.2
0	127	127	0
2	125.5	127.5	0.8
4	124.5	128.5	2.9
8	123.5	131.5	9.2

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FIG. 5

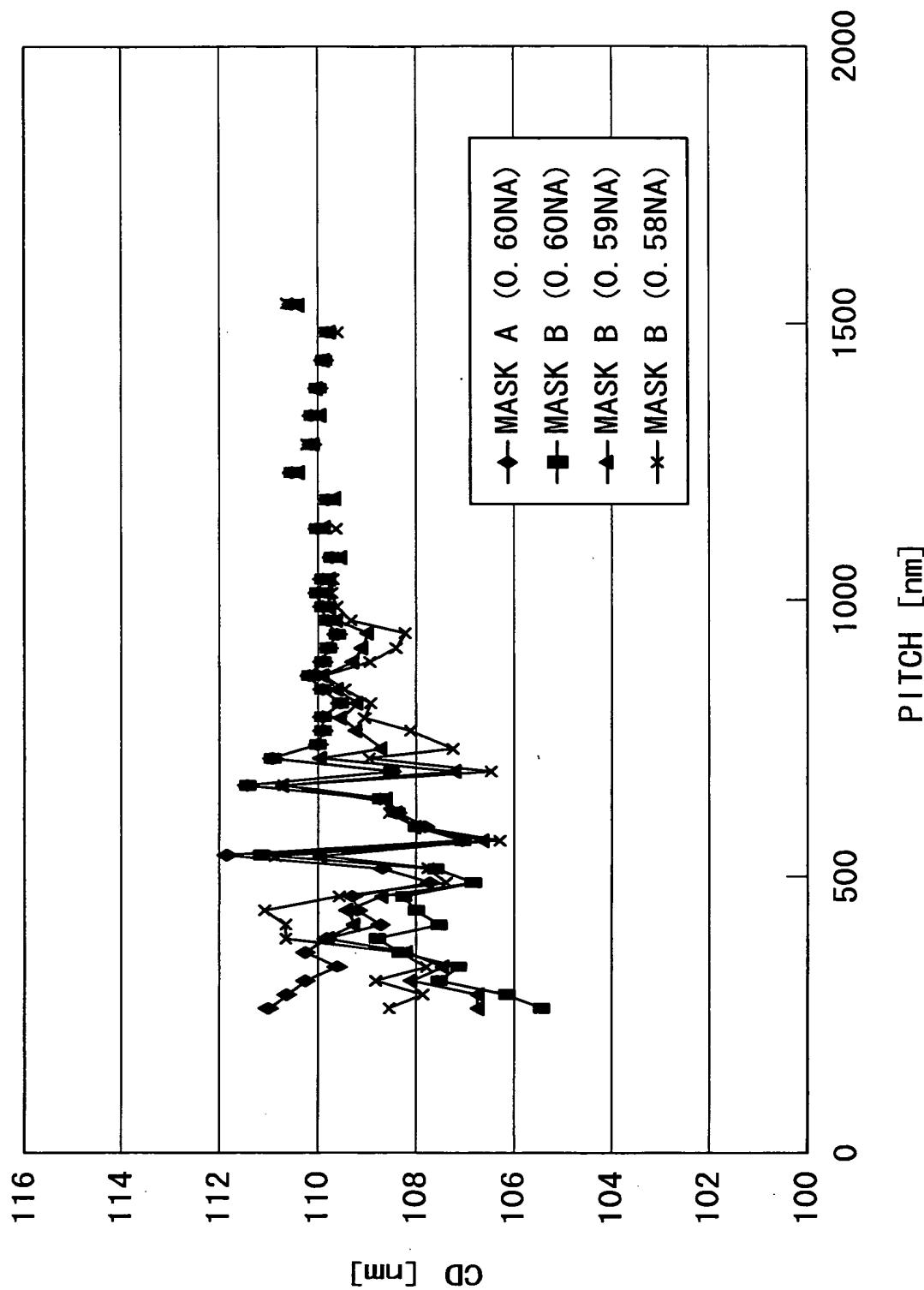


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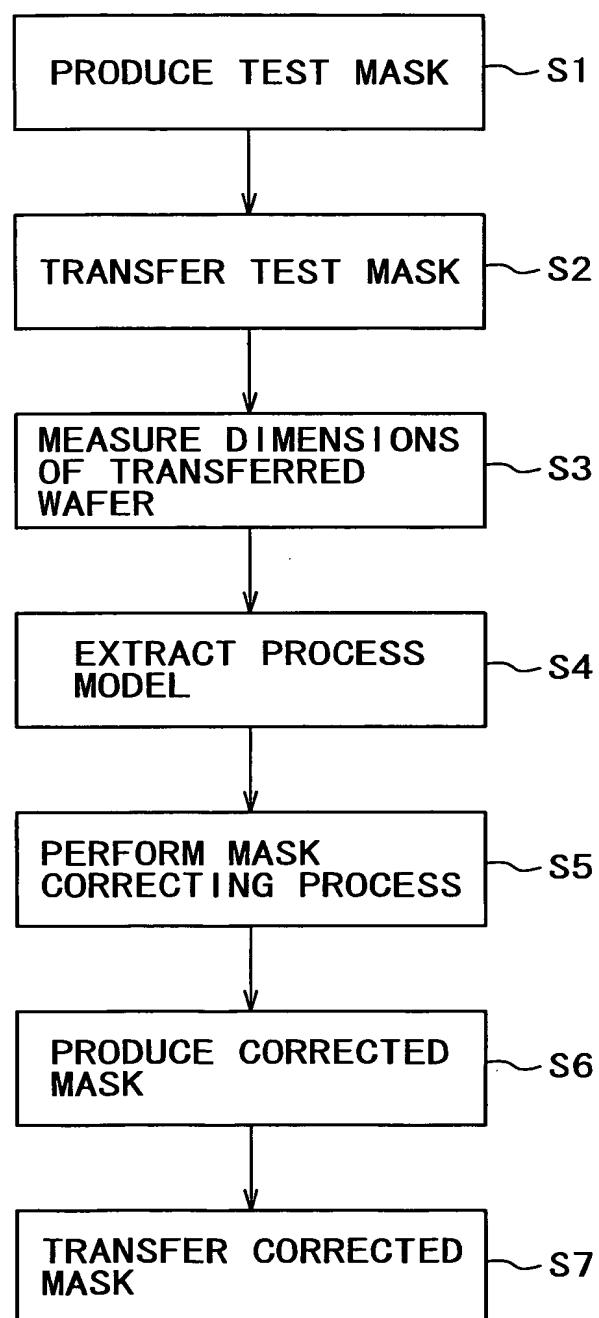
FIG. 6



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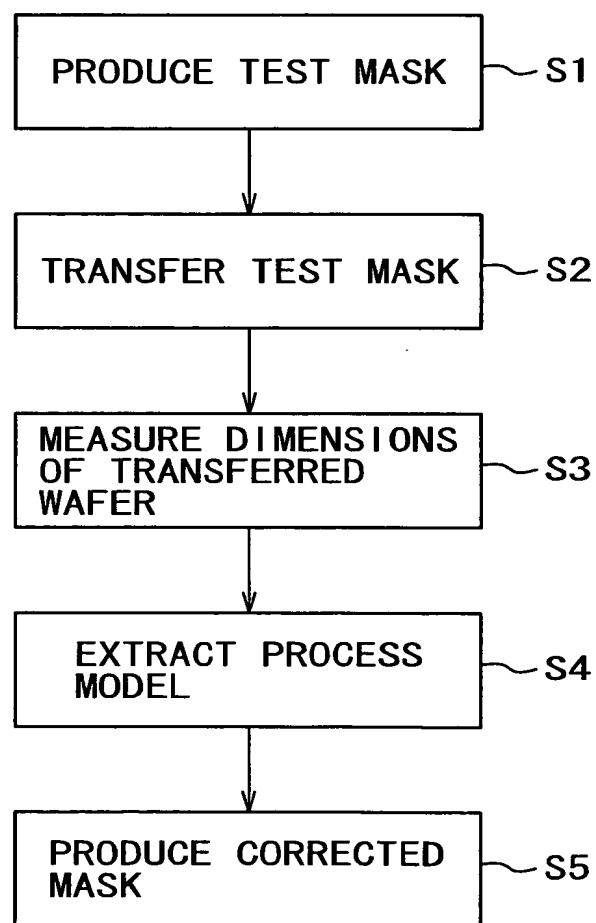
F I G. 7



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F I G. 8

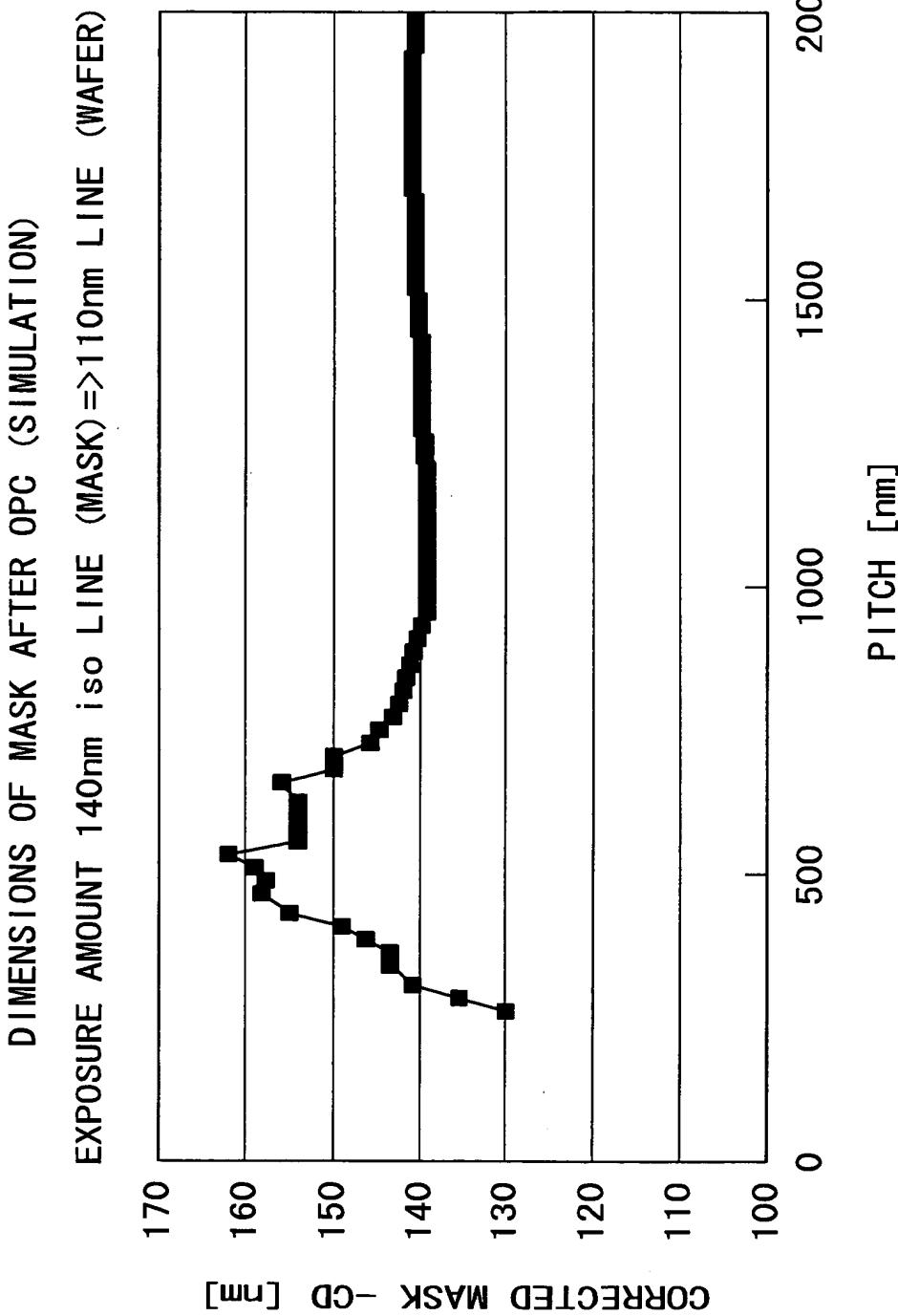


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FIG. 9



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F I G. 1 0

ERROR OF LINE WIDTH DEPENDING ON
COARSE/DENSE OF MASK B (ON WAFER)
(TARGET=140nm LINE, THROUGH-PITCH)

